| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|---|---|---|---|---|---|---|
| L1 | 357963 | (plasma cvd ALD (atomic near5 layer near5 deposit$3) (chemical near5 vapor near5 deposit$3)) | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 12:05 |
| L2 | 24311 | 1 and (BPSG PSG (borophosphosilicate near5 glass) (dop$3 near5 silicon near5 (oxide dioxide))) | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 12:05 |
| L3 | 1158 | 2 and ( phosphorus near5 dop$3 near5 silicon near5 (oxide dioxide)) | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 12:06 |
| L4 | 0 | 3 and ( "Si" near3 "OR"".sub. 3" near3 "OH") | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 11:54 |
| L5 | 810 | ("PO" near5 "OR") | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 11:56 |
| L6 | 269 | ("Si" near5 "OR" near5 "OH") | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 11:56 |
| L7 | 9 | 5 and 6 | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 11:57 |
| L8 | 402 | ("PO" near5 "O" near5 "CH") | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 11:58 |
| L9 | 85 | ("Si" near5 "O" near5 "CH" near5 "OH") | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 11:58 |
| L10 | 0 | 8 and 9 | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 11:59 |
| L11 | 487 | 8 9 | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 11:59 |
| L12 | 0 | 3 and 11 | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 11:59 |
| L13 | 29461 | hydrocarbyl hydro-carbyl | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 12:00 |
| L14 | 5 | 13 and 3 | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 12:00 |

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|---|---|---|---|---|---|---|
| L2 | 3142 | chemisorb$3 | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 17:44 |
| L3 | 2835 | 2 and (silicon (oxide dioxide)) | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 17:44 |
| L4 | 503 | 3 and phosphorus | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 17:45 |
| L5 | 215 | 4 and (pulse cvd plasma (chemical near5 vapor near5 deposit$3)) | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 16:23 |
| L7 | 215 | 4 and (pulse cvd ALD (atomic near5 layer near5 deposit$3) plasma (chemical near5 vapor near5 deposit$3)) | US-PGPUB; USPAT; USOCR | OR | ON | 2005/07/05 16:24 |
| L8 | 420 | chemisorb$3 | EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/05 17:44 |
| L9 | 130 | 8 and (silicon (oxide dioxide)) | EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/05 17:44 |
| L10 | 3 | 9 and phosphorus | EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/05 17:45 |

| L15 | 232980 | (plasma cvd ALD (atomic near5 layer near5 deposit$3) (chemical near5 vapor near5 deposit$3)) | EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/05 12:05 |
|-----|--------|---|---|----|----|---|
| L16 | 2074 | 15 and (BPSG PSG (borophosphosilicate near5 glass) (dop$3 near5 silicon near5 (oxide dioxide))) | EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/05 12:06 |
| L17 | 38 | 16 and ( phosphorus near5 dop$3 near5 silicon near5 (oxide dioxide)) | EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/05 12:06 |